

A general stress patterning method for manufacturing ultra-precise free-form deformation in thin-substrates (Withdrawal Notice)

Youwei Yao, Brandon Chalifoux, Ralf Heilmann, Mark Schattenburg

Proceedings Volume 11822, [Optics for EUV, X-Ray, and Gamma-Ray Astronomy X](#);118220W (2021)

<https://doi.org/10.1117/12.2595537>

Event: Optics for EUV, X-Ray, and Gamma-Ray Astronomy X, 2021, San Diego, California, United States

Online Publication Date: 5 August 2021

Withdrawn from Publication: 13 August 2021

Publisher's Note: This conference presentation, originally published on 5 August 2021 was withdrawn on 13 August 2021 per author request.